

Appl. No. 10/044,271

Amdt. Dated Jun. 23, 2005

Reply to Office Action of Mar. 23, 2005

**Amendments to the Abstract:**

Please amend the abstract as follows:

**Methods** A method for making thin film filters having a negative temperature drift coefficient are the subject of the present invention. Such filters can achieve better optical control within an operational temperature range from  $[-5]$  -5°C to 70°C degrees ~~centigrade~~. A first embodiment ~~of the present invention~~ includes ~~the steps of~~: 1. providing a substrate wafer which has a coefficient of thermal expansion (CTE) greater than that of a selected film stack material; 2. polishing the substrate wafer; 3. depositing thin film layers made of the film stack material on the substrate wafer at a temperature substantially higher than room temperature; 4. cooling the substrate-film stack laminate to room temperature, thus forming a convex-shaped laminate; 5. cutting the cooled laminate into pieces. A second embodiment includes the steps of: 1. providing a laminate ~~compose~~ composed of a glass substrate and a film stack; 2. using at least one ion beam source to bombard the film stack of the laminate with high energy ions; 3. cutting the bombarded laminate into pieces.